

References

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2. K. Vedam, "Spectroscopic Ellipsometry: A Historical Overview," *Thin Solid Films*, Vol. 313-314, No. 1-2, 1998, p. 1.
3. R.M.A. Azzam and N.M. Bashara, *Ellipsometry and Polarized Light*, North Holland, Amsterdam, 1997.
4. A.R. Srivatsa and C. Ygartua, *Optical Metrology*, Ghanim Al-Jumaily, Ed., SPIE Optical Engineering Press, 1999, p. 61.

KLA-Tencor Trade Show Calendar

March 11-13	SEMICON China, Shanghai, China
March 24-26	IC China, Shanghai, China
April 1-3	SEMICON Europa, Munich, Germany
April 10-12	DISKCON Japan, Tokyo, Japan
April 16-18	Photomask Japan, Yokohama, Japan
July 14-16	SEMICON West, San Francisco, California
July 16-18	SEMICON West, San Jose, California